Contribution ID: **92** Type: **Študenti fyzika**

OPTIMISATION OF THE LITHOGRAPHY AND PYROLYSIS PROCESS OF SU-8 RESIST FOR FABRICATION OF CONDUCTIVE MICROSTRUCTURES

Wednesday, November 26, 2025 11:05 AM (1 minute)

This work presents the fabrication and characterization of carbon microstructures from SU-8 photoresist by rapid thermal pyrolysis. The aim was to optimize lithography
and pyrolysis parameters to obtain conductive microstructures for sensor use. Structures were prepared on Si/SiO_2 and Al_2O_3 substrates and pyrolyzed up to 1200 ℃
in nitrogen. The effect of temperature and dwell time on electrical properties was studied, showing that higher temperatures and longer dwell times lower electrical
resistance. The results confirm rapid thermal pyrolysis as an efficient, low-cost method for producing carbon microelectrodes for sensor applications.

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Authors: DURINA, Pavol (Comenius University in Bratislava. FMPI); ROCH, Tomáš (Comenius University in Bratislava, FMPI, CENAM); PLECENIK, Tomáš (Centre for Nanotechnology and Advanced Materials, Faculty of Mathematics, Physics and Informatics, Comenius University Bratislava); KECEROVÁ, Adriana; Dr ŠKRINIROVÁ, Jaroslava

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